

PHOTORESIST COMPOSITIONS COMPRISING POLYCYCLIC POLYMERS WITH ACID LABILE PENDANT GROUPS

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Inventor(s):

Applicant(s):

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C08F232/00; C08G61/00; G03F7/023; G03F7/039; (IPC1-
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WO9914256 (A1)

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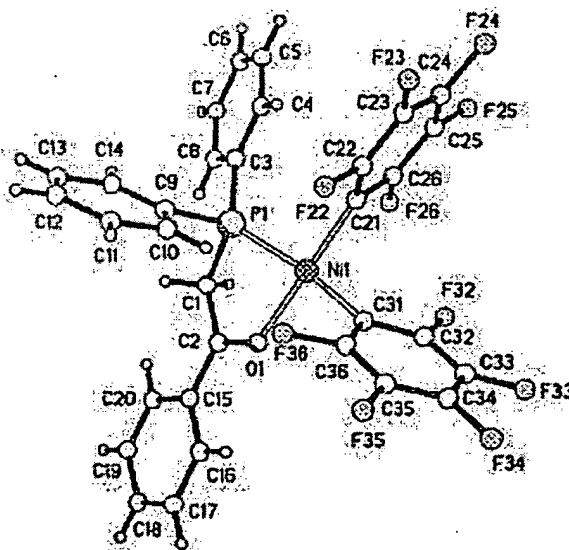
AU748214 (B2)

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Abstract not available for JP 2001516780 (T)

Abstract of corresponding document: **WO 9914256 (A1)**

The present invention relates to a radiation sensitive photoresist composition comprising a photoacid initiator and a polycyclic polymer comprising repeating units that contain pendant acid labile groups. Upon exposure to an imaging radiation source the photoacid initiator generates an acid which cleaves the pendant acid labile groups effecting a polarity change in the polymer. The polymer is rendered soluble in an aqueous base in the areas exposed to the imaging source.



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PHOTORESIST COMPOSITIONS COMPRISING POLYCYCLIC POLYMERS WITH ACID LABILE PENDANT GROUPS

Publication number: WO9914256 (A1)

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Inventor(s): RHODES LARRY F; BELL ANDREW; JAYARAMAN SAIKUMAR; LIPIAN JOHN-HENRY; GOODALL BRIAN L; SHICK ROBERT A

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Classification:






- international: **C08F232/00; C08G61/08; G03F7/023; G03F7/039; C08F232/00; C08G61/00; G03F7/023; G03F7/039; (IPC1-7): C08G61/08; G03F7/023**

- European: **C08G61/08; G03F7/039**

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 WO9914256 (A8)
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Cited documents:

 EP0789278 (A2)
 WO9720871 (A2)
 WO9733198 (A1)

Abstract of WO 9914256 (A1)

The present invention relates to a radiation sensitive photoresist composition comprising a photoacid initiator and a polycyclic polymer comprising repeating units that contain pendant acid labile groups. Upon exposure to an imaging radiation source the photoacid initiator generates an acid which cleaves the pendant acid labile groups effecting a polarity change in the polymer. The polymer is rendered soluble in an aqueous base in the areas exposed to the imaging source.

